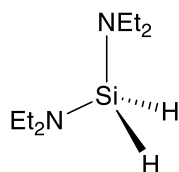


Catalog # 14-7030 Bis(diethylamino)silane, 97% BDEAS



Technical Notes:

1. Plasma-Assisted ALD for the Conformal Deposition of SiO₂
2. Room-Temperature ALD of Metal Oxide Thin Films by Energy-Enhanced ALD
3. Atomic Layer Deposition of Silica on Carbon Nanotubes
4. Area-Selective Atomic Layer Deposition of SiO₂ Using Acetylacetone as a Chemoselective Inhibitor in an ABC-Type Cycle

References:

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2. *Chem. Vap. Deposition*, **2013**, *19*, 125.
3. *Chem. Mater.*, **2017**, *29*, 4920.
4. *ACS Nano*, **2017**, *11*, 9303.